

MgO-TiO SINTERED COMPACT TARGET AND METHOD FOR PRODUCING SAME

ABSTRACT

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A MgO-TiO sintered compact comprising TiO in an amount of 25 to 90 mol%, and remainder being MgO and unavoidable impurities. An object of the present invention is to provide a high density target having a high deposition rate and which can be subject to direct current (DC) sputtering with low generation of particles, and a method for producing such a target.

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Fig. 1

